

Title (en)  
DEVICE AND METHOD FOR PRODUCING LAYERS WITH IMPROVED UNIFORMITY IN COATING SYSTEMS WITH HORIZONTALLY ROTATING SUBSTRATE AND ADDITIONAL PLASMA SOURCES

Title (de)  
VORRICHTUNG UND VERFAHREN ZUR HERSTELLUNG VON SCHICHTEN MIT VERBESSERTER UNIFORMITÄT BEI BESCHICHTUNGSANLAGEN MIT HORIZONTAL ROTIERENDER SUBSTRATFÜHRUNG MIT ZUSÄTZLICHEN PLASMAQUELLEN

Title (fr)  
DISPOSITIF ET PROCÉDÉ DE PRODUCTION DE COUCHES À UNIFORMITÉ AMÉLIORÉE DANS DES SYSTÈMES DE REVÊTEMENT À SUBSTRAT TOURNANT HORIZONTALEMENT ET SOURCES DE PLASMA SUPPLÉMENTAIRES

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Application  
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Abstract (en)  
[origin: WO2021160786A1] The invention relates to a device and a method for producing layers whose layer thickness distribution can be adjusted in coating systems with horizontally rotating substrate. A very homogeneous or a specific non-homogeneous distribution can be adjusted. The particle loading is also significantly reduced. The service life is significantly higher compared to other methods. Forming of parasitic coatings is reduced.

IPC 8 full level  
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**C23C 14/0036** (2013.01 - US); **C23C 14/351** (2013.01 - EP US); **C23C 14/352** (2013.01 - EP); **C23C 14/357** (2013.01 - EP US); **C23C 14/505** (2013.01 - EP US); **C23C 14/52** (2013.01 - EP); **C23C 14/547** (2013.01 - EP US); **H01J 37/32192** (2013.01 - EP); **H01J 37/32201** (2013.01 - US); **H01J 37/32366** (2013.01 - US); **H01J 37/32715** (2013.01 - US); **H01J 37/32779** (2013.01 - EP); **H01J 37/32935** (2013.01 - EP); **H01J 37/3299** (2013.01 - EP); **H01J 37/3405** (2013.01 - EP US); **H01J 37/3476** (2013.01 - US); **H01J 2237/20214** (2013.01 - US); **H01J 2237/24585** (2013.01 - US); **H01J 2237/332** (2013.01 - US)

Citation (search report)  
See references of WO 2021160786A1

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